

Chemicals supplied to NRF Users

Acids

Sulfuric Acid - H ₂ SO ₄	chrome etch 1020
BOE 6:1 – NH ₄ F/HF	Aluminum etch
Hydrochloric acid - HCL	iron oxide mask etch
Phosphoric acid – H ₃ PO ₄	chrome mask etch
Hydrofluoric acid - HF	Freckle Etch
Nitric acid – HNO ₃	Iron Oxide Mask Etch
gold etch	

Bases

Ammonium hydroxide – NH ₄ OH
Hydrogen Peroxide – H ₂ O ₂

General Solvents

Propanol (Isopropanol)(2-propanol)
Methanol
Acetone

Photolithography

AZ1512
Kemlab KL6008
AZ9260
AZ nLOF 2035
Microchem LOR-A
Microchem 950PMMA A2
Microchem 950PMMA A4
Microchem 950PMMA A6
MIBK/IPA (1:3)
Technistrip MLO 07
AZ EBR (aka PGMEA)
NMP (AZ NMP Rinse)
SU8 Developer (aka PGMEA)

Special Notes about chemicals:

- Small quantities for pipette dispensing the following photochemicals may be found in the Litho Bay rack, lower shelf.

AZ1512

Kemlab KL6008

AZ 9260

nLOF 2035

LOR3A

PMMA is located in the Ebeam Bay solvent bench, lower right door.